

The documentation and process conversion measures necessary to comply with this revision shall be completed by 1 January 2015.

INCH-POUND

MIL-PRF-19500/746C
17 November 2014
SUPERSEDING
MIL-PRF-19500/746B
24 June 2011

PERFORMANCE SPECIFICATION SHEET

TRANSISTOR, FIELD EFFECT, RADIATION HARDENED, N-CHANNEL,
SILICON, SURFACE MOUNT, TYPES 2N7587, 2N7589, 2N7591,
AND 2N7593, QUALITY LEVELS JANTXV and JANS

This specification is approved for use by all Departments
and Agencies of the Department of Defense.

The requirements for acquiring the product described herein shall consist of
this specification sheet and [MIL-PRF-19500](#).

1. SCOPE

1.1 Scope. This specification covers the performance requirements for a N-channel, enhancement-mode, MOSFET, radiation hardened (total dose and single event effects (SEE)), power transistor.

1.2 Package outlines. The device package outline is a TO-276AA in accordance with [figure 1](#) for all encapsulated device types.

1.3 Maximum ratings. $T_A = +25^\circ\text{C}$, unless otherwise specified.

Type	P_T (1) $T_C = +25^\circ\text{C}$	P_T $T_A = +25^\circ\text{C}$	$R_{\theta JC}$ (2)	V_{DS}	V_{DG}	V_{GS}	I_{D1} (3) (4) $T_C = +25^\circ\text{C}$	I_{D2} $T_C = +100^\circ\text{C}$	I_S	I_{DM} (5)	T_J and T_{STG}	V_{ISO} 70,000 ft. altitude
	<u>W</u>	<u>W</u>	<u>$^\circ\text{C/W}$</u>	<u>V dc</u>	<u>V dc</u>	<u>V dc</u>	<u>A dc</u>	<u>A dc</u>	<u>A dc</u>	<u>A (pk)</u>	<u>$^\circ\text{C}$</u>	<u>V dc</u>
2N7587U3, 2N7587U3C	75	1.56	1.67	100	100	± 20	22	19	22	88		
2N7589U3, 2N7589U3C	75	1.56	1.67	150	150	± 20	19	12	19	76	-55 to +150	
2N7591U3, 2N7591U3C	75	1.56	1.67	200	200	± 20	16	10	16	64		
2N7593U3, 2N7593U3C	75	1.56	1.67	250	250	± 20	12.4	7.8	12.4	49.6		250

(1) Derate linearly by 0.6 W/ $^\circ\text{C}$ for $T_C > +25^\circ\text{C}$.

(2) See [figure 2](#), thermal impedance curves.

(3) The following formula derives the maximum theoretical I_D limit. I_D is limited by package and internal wires and may be limited by pin diameter:

$$I_D = \sqrt{\frac{T_{JM} - T_C}{(R_{\theta JC}) \times (R_{DS(on)} \text{ at } T_{JM})}}$$

(4) See [figure 3](#), maximum drain current graph.

(5) $I_{DM} = 4 \times I_{D1}$; I_{D1} as calculated by footnote (3).

* Comments, suggestions, or questions on this document should be addressed to DLA Land and Maritime, ATTN: VAC, P.O. Box 3990, Columbus, OH 43218-3990, or emailed to Semiconductor@dla.mil. Since contact information can change, you may want to verify the currency of this address information using the ASSIST Online database at <https://assist.dla.mil/>.

* 1.4 Primary electrical characteristics at TC = +25°C.

Type	Min $V_{(BR)DSS}$ $V_{GS} = 0$ $I_D = 1.0\text{mA dc}$	$V_{GS(TH)1}$ $V_{DS} \geq V_{GS}$ $I_D = 1.0\text{ mA dc}$	Max I_{DSS1} $V_{GS} = 0$ $V_{DS} = 80\%$ of rated V_{DS}	Max $r_{DS(on)}$ (1) $V_{GS} = 12\text{V}$, $I_D = I_{D2}$		E_{AS}
				$T_J = +25^\circ\text{C}$	$T_J = +150^\circ\text{C}$	
	<u>V dc</u>	<u>V dc</u> Min Max	<u>$\mu\text{A dc}$</u>	<u>Ω</u>	<u>Ω</u>	<u>mJ</u>
2N7587U3, 2N7587U3C	100	2.0 4.0	10	0.042	0.084	73
2N7589U3, 2N7589U3C	150	2.0 4.0	10	0.088	0.207	60
2N7591U3, 2N7591U3C	200	2.0 4.0	10	0.130	0.300	60
2N7593U3, 2N7593U3C	250	2.0 4.0	10	0.210	0.494	56

(1) Pulsed (see 4.5.1).

* 1.5 Part or Identifying Number (PIN). The PIN is in accordance with [MIL-PRF-19500](#), and as specified herein. See 6.6 for PIN construction example and 6.7 for a list of available PINs.

* 1.5.1 JAN certification mark and quality level. The only quality level designator for encapsulated devices that is applicable for this specification sheet are the quality levels "JANTXV" and "JANS".

* 1.5.2 Radiation hardness assurance (RHA) designator. The RHA levels that are applicable for this specification sheet from lowest to highest are as follows: "R" and "F".

* 1.5.3 Device type. The designation system for the device types of transistors covered by this specification sheet are as follows.

* 1.5.3.1 First number and first letter symbols. The transistor of this specification sheet use the first number and letter symbols "2N".

* 1.5.3.2 Second number symbols. The second number symbols for the transistors covered by this specification sheet are as follows: "7587", "7589", "7591" and "7593".

* 1.5.4 Suffix letters. The following suffix letters are incorporated in the PIN for this specification sheet:

U3	Indicates a metal lidded 3 pad surface mount package similar to a TO-276AA (SMD-0.5) (see figure 1).
U3C	Indicates a ceramic lidded 3 pad surface mount package similar to a TO-276AA (SMD-0.5) (see figure 1).

* 1.5.5 Lead finish designator. The lead finishes applicable to this specification sheet are listed on [QML-19500](#).

2. APPLICABLE DOCUMENTS

* 2.1 General. The documents listed in this section are specified in sections 3 and 4 of this specification. This section does not include documents cited in other sections of this specification or recommended for additional information or as examples. While every effort has been made to ensure the completeness of this list, document users are cautioned that they must meet all specified requirements of documents cited in sections 3 and 4 of this specification, whether or not they are listed.

2.2 Government documents.

2.2.1 Specifications, standards, and handbooks. The following specifications, standards, and handbooks form a part of this document to the extent specified herein. Unless otherwise specified, the issues of these documents are those cited in the solicitation or contract.

DEPARTMENT OF DEFENSE SPECIFICATIONS

[MIL-PRF-19500](#) - Semiconductor Devices, General Specification for.

DEPARTMENT OF DEFENSE STANDARDS

[MIL-STD-750](#) - Test Methods for Semiconductor Devices.

(Copies of these documents are available online at <http://quicksearch.dla.mil/>.)

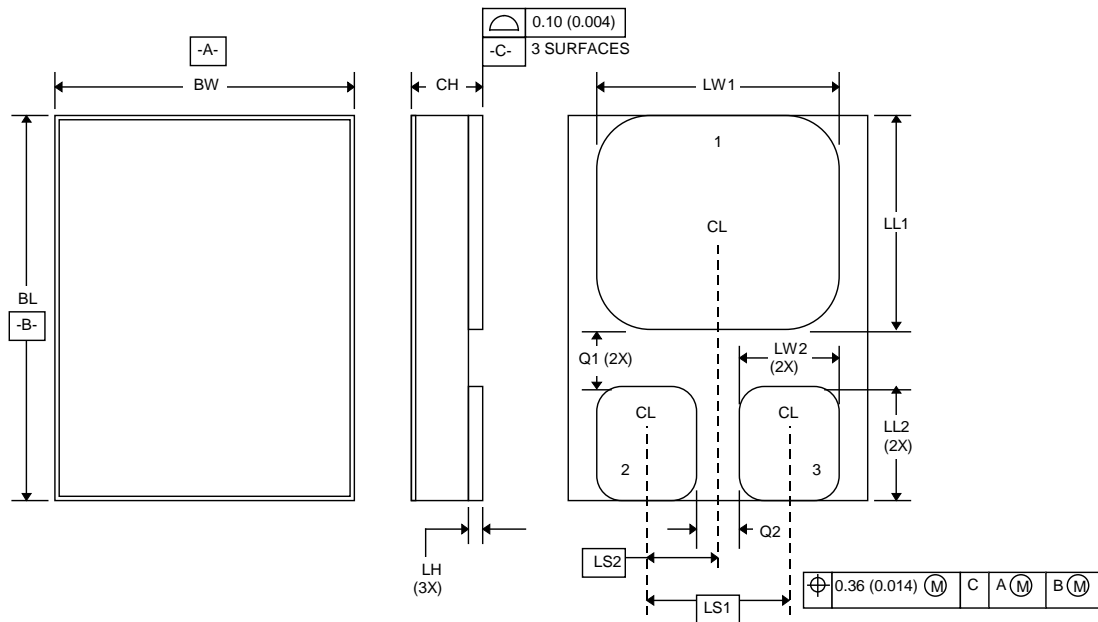
2.3 Order of precedence. Unless otherwise noted herein or in the contract, in the event of a conflict between the text of this document and the references cited herein, the text of this document takes precedence. Nothing in this document, however, supersedes applicable laws and regulations unless a specific exemption has been obtained.

3. REQUIREMENTS

- * 3.1 General. The individual item requirements shall be as specified in [MIL-PRF-19500](#) and as specified herein.
- 3.2 Qualification. Devices furnished under this specification shall be products that are manufactured by a manufacturer authorized by the qualifying activity for listing on the applicable qualified manufacturer's list (QML) before contract award (see [4.2](#) and [6.3](#)).
- 3.3 Abbreviations, symbols, and definitions. Abbreviations, symbols, and definitions used herein shall be as specified in [MIL-PRF-19500](#).
- * 3.4 Interface requirements and physical dimensions. The interface and requirements physical dimensions shall be as specified in [MIL-PRF-19500](#) and herein. The device package style is either a metal lidded or ceramic lidded TO-276AA in accordance with [figure 1](#) for all device types.
- * 3.4.1 Lead finish. The lead finishes applicable to this specification sheet are listed on [QML-19500](#). Unless otherwise specified, lead finish shall be solderable in accordance with [MIL-PRF-19500](#), [MIL-STD-750](#), and herein. Where a choice of lead finish is desired, it shall be specified in the acquisition document (see [6.2](#)).
- 3.4.2 Multiple chip construction. Multiple chip construction is not permitted to meet the requirements of this specification.
- * 3.4.3 Pin-out. The pin-out of the device shall be as shown on figure 1.
- * 3.5 Marking. Marking shall be in accordance with MIL-PRF-19500.
- * 3.6 Electrical performance characteristics. Unless otherwise specified herein, the electrical performance characteristics are as specified in [1.3](#), [1.4](#) and [table I](#).
- * 3.7 Workmanship. Transistors shall be processed in such a manner as to be uniform in quality and shall be free from other defects that will affect life, serviceability, or appearance.

4. VERIFICATION

- 4.1 Classification of inspections. The inspection requirements specified herein are classified as follows:
 - a. Qualification inspection (see [4.2](#)).
 - b. Screening (see [4.3](#)).
 - c. Conformance inspection (see [4.4](#) and [tables I and II](#)).



Symbol	Dimensions			
	Inches		Millimeters	
	Min	Max	Min	Max
BL	.395	.405	10.04	10.28
BW	.291	.301	7.40	7.64
CH (for U3)		.124		3.15
CH (for U3C)		.1335		3.39
LH	.010	.020	0.25	0.51
LW1	.281	.291	7.14	7.39
LW2	.090	.100	2.29	2.54
LL1	.220	.230	5.59	5.84
LL2	.115	.125	2.93	3.17
LS1	.150 BSC		3.81 BSC	
LS2	.075 BSC		1.91 BSC	
Q1	.030		0.762	
Q2	.030		0.762	
TERM 1	Drain			
TERM 2	Gate			
TERM 3	Source			

NOTES:

1. Dimension are in inches.
2. Millimeters are given for information only.
3. The lid shall be electrically isolated from the drain, gate, and source.
4. In accordance with ASME Y14.5M, diameters are equivalent to ϕ x symbology.
5. Metal lid: U3 suffix; Ceramic lid: U3C suffix.

FIGURE 1. Dimensions and configuration (TO-276AA, SMD-0.5), with metal lid or ceramic lid.

- * 4.2 Qualification inspection. Qualification inspection shall be in accordance with [MIL-PRF-19500](#) and as specified herein.

4.2.1 Group E qualification. Group E inspection shall be performed for qualification or re-qualification only. In case qualification was awarded to a prior revision of the specification sheet that did not request the performance of [table III](#) tests, the tests specified in [table III](#) herein that were not performed in the prior revision shall be performed on the first inspection lot of this revision to maintain qualification.

- * 4.3 Screening of encapsulated devices. Screening of packaged devices shall be in accordance with table E-IV of [MIL-PRF-19500](#), and as specified herein. The following measurements shall be made in accordance with [table I](#) herein. Devices that exceed the limits of [table I](#) herein shall not be acceptable.

Screen (1) (2)	Measurement	
	JANS	JANTXV
(3)	Gate stress test (see 4.3.1)	Gate stress test (see 4.3.1)
(3)	Method 3470 of MIL-STD-750 , E_{AS} (see 4.3.2)	Method 3470 of MIL-STD-750 , E_{AS} (see 4.3.2)
(3) 3c	Method 3161 of MIL-STD-750 , thermal impedance, (see 4.3.3)	Method 3161 of MIL-STD-750 , thermal impedance, (see 4.3.3)
9	Subgroup 2 of table I herein I_{GSSF1} , I_{GSSR1} , I_{DSS1} as a minimum	Not applicable
10	Method 1042 of MIL-STD-750 , test condition B	Method 1042 of MIL-STD-750 , test condition B
11	I_{GSSF1} , I_{GSSR1} , I_{DSS1} , $r_{DS(ON)1}$, $V_{GS(TH)1}$ Subgroup 2 of table I herein. $\Delta I_{GSSF1} = \pm 20$ nA dc or ± 100 percent of initial value, whichever is greater. $\Delta I_{GSSR1} = \pm 20$ nA dc or ± 100 percent of initial value, whichever is greater. $\Delta I_{DSS1} = \pm 10$ μ A dc or ± 100 percent of initial value, whichever is greater.	I_{GSSF1} , I_{GSSR1} , I_{DSS1} , $r_{DS(ON)1}$, $V_{GS(TH)1}$ Subgroup 2 of table I herein.
12	Method 1042 of MIL-STD-750 , test condition A	Method 1042 of MIL-STD-750 , test condition A
13	Subgroups 2 and 3 of table I herein $\Delta I_{GSSF1} = \pm 20$ nA dc or ± 100 percent of initial value, whichever is greater. $\Delta I_{GSSR1} = \pm 20$ nA dc or ± 100 percent of initial value, whichever is greater. $\Delta I_{DSS1} = \pm 10$ μ A dc or ± 100 percent of initial value, whichever is greater. $\Delta r_{DS(ON)1} = \pm 20$ percent of initial value. $\Delta V_{GS(TH)1} = \pm 20$ percent of initial value.	Subgroup 2 of table I herein $\Delta I_{GSSF1} = \pm 20$ nA dc or ± 100 percent of initial value, whichever is greater. $\Delta I_{GSSR1} = \pm 20$ nA dc or ± 100 percent of initial value, whichever is greater. $\Delta I_{DSS1} = \pm 10$ μ A dc or ± 100 percent of initial value, whichever is greater. $\Delta r_{DS(ON)1} = \pm 20$ percent of initial value. $\Delta V_{GS(TH)1} = \pm 20$ percent of initial value.
17	For TO-276AA packages: Method 1081 of MIL-STD-750 (see 4.3.4), Endpoints: Subgroup 2 of table I herein.	For TO-276AA packages: Method 1081 of MIL-STD-750 (see 4.3.4), Endpoints: Subgroup 2 of table I herein.

- (1) At the end of the test program, I_{GSSF1} , I_{GSSR1} , and I_{DSS1} are measured.
 (2) An out-of-family program to characterize I_{GSSF1} , I_{GSSR1} , I_{DSS1} and $V_{GS(th)1}$ shall be invoked.
 (3) Shall be performed anytime after temperature cycling, screen 3a; JANTXV does not need to be repeated in screening requirements.

4.3.1 Gate stress test. Apply $V_{GS} = 24$ V minimum for $t = 250$ μ s minimum.

4.3.2 Single pulse avalanche energy (E_{AS}).

a. Peak current $I_{AS} = I_{D1}$.

b. Inductance: $\left[\frac{2E_{AS}}{(I_{D1})^2} \right] \left[\frac{V_{BR} - V_{DD}}{V_{BR}} \right]$ mH minimum.

c. Gate to source resistor (R_{GS}) $25 \leq R_{GS} \leq 200 \Omega$.

d. Supply voltage (V_{DD}) $V_{DD} = 25$ V dc, except $V_{DD} = 50$ V dc (2N7593), up to rated V_{DS} .

e. Peak gate voltage (V_{GS}) 12 V, up to maximum rated V_{GS} .

f. Initial case temperature $T_C = +25^\circ\text{C} + 10^\circ\text{C}, -5^\circ\text{C}$.

g. Number of pulses to be applied 1 pulse minimum.

4.3.3 Thermal impedance. The thermal impedance measurements shall be performed in accordance with method 3161 of [MIL-STD-750](#) using the guidelines in that method for determining I_M , I_H , t_H , t_{SW} , (and V_H where appropriate). Measurement delay time (t_{MD}) = 30 - 60 μ s max. See [table III](#), group E, subgroup 4 herein.

* 4.3.4 Dielectric withstanding voltage.

a. Magnitude of test voltage 600V dc.

b. Duration of application of test voltage 15 seconds (min).

c. Points of application of test voltage All leads to case (bunch connection).

d. Method of connection Mechanical.

e. Kilovolt-ampere rating of high voltage source 1,200 V/1.0 mA (min).

f. Maximum leakage current 1.0 mA.

g. Voltage ramp up time 500 V/second

4.4 Conformance inspection. Conformance inspection shall be in accordance with [MIL-PRF-19500](#).

4.4.1 Group A inspection. Group A inspection shall be conducted in accordance with table E-V of [MIL-PRF-19500](#) and [table I](#) herein.

* 4.4.2 Group B inspection. Group B inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-VIA (JANS) and table E-VIB (JANTXV) of [MIL-PRF-19500](#), and as follows.

- * 4.4.2.1 Quality level JANS (table E-VIA of MIL-PRF-19500).

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
B3	1051	Test condition G, 100 cycles.
B3	2077	Scanning electron microscope (SEM).
B4	1042	Intermittent operation life, condition D; $t_{on} = 30$ seconds minimum.
B5	1042	Accelerated steady-state gate bias, condition B, $V_{GS} = \text{rated}$; $T_A = +175^\circ\text{C}$, $t = 24$ hours minimum; or $T_A = +150^\circ\text{C}$, $t = 48$ hours minimum.
B5	1042	Accelerated steady-state reverse bias, condition A, $V_{DS} = \text{rated}$; $T_A = +175^\circ\text{C}$, $t = 120$ hours minimum; or $T_A = +150^\circ\text{C}$, $t = 240$ hours minimum.
B5	2037	Test condition D.

- 4.4.2.2 Quality level JANTXV (table E-VIB of MIL-PRF-19500).

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
B2	1051	Test condition G, 25 cycles.
B3	1042	Intermittent operation life, condition D, $t_{on} = 30$ seconds minimum.

- * 4.4.3 Group C inspection. Group C inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-VII of MIL-PRF-19500 and as follows.

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
C2	2036	Terminal strength is not applicable.
C5	3161	See 4.3.3, $R_{\theta JC} = 1.67^\circ\text{C/W}$.
C6	1042	Intermittent operation life, condition D, $t_{on} = 30$ seconds minimum.

- 4.4.4 Group D inspection. Group D inspection shall be conducted in accordance with table E-VIII of MIL-PRF-19500 and table II herein.

- * 4.4.5 Group E inspection. Group E inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-IX of MIL-PRF-19500 and as specified in table III herein.

4.4.5.1 SEE. Design capability shall be tested on the initial qualification and thereafter whenever a major die design or process change is introduced. See table IV and the safe operation area graph herein. Electrical measurements (end-points) shall be in accordance with table III herein.

- 4.5 Methods of inspection. Methods of inspection shall be as specified in the appropriate tables and as follows.

- 4.5.1 Pulse measurements. The conditions for pulse measurement shall be as specified in section 4 of MIL-STD-750.

TABLE I. Group A inspection.

Inspection <u>1/</u>	MIL-STD-750		Symbol	Limits		Unit
	Method	Condition		Min	Max	
<u>Subgroup 1</u>						
Visual and mechanical inspection	2071					
<u>Subgroup 2</u>						
Thermal impedance <u>2/</u>	3161	See 4.3.3	$Z_{\theta JC}$			°C/W
Breakdown voltage drain to source	3407	Bias condition C, $V_{GS} = 0$ V, $I_D = 1$ mA dc	$V_{(BR)DSS}$	100		V dc
2N7587U3, 2N7587U3C				150		V dc
2N7589U3, 2N7589U3C				200		V dc
2N7591U3, 2N7591U3C				250		V dc
2N7593U3, 2N7593U3C						
Gate to source voltage (threshold)	3403	$V_{DS} \geq V_{GS}$, $I_D = 1$ mA dc	$V_{GS(TH)1}$	2.0	4.0	V dc
Gate current	3411	$V_{GS} = +20$ V dc, bias condition C, $V_{DS} = 0$ V	I_{GSSF1}		+100	nA dc
Gate current	3411	$V_{GS} = -20$ V dc, bias condition C, $V_{DS} = 0$ V	I_{GSSR1}		-100	nA dc
Drain current	3413	$V_{GS} = 0$ V dc, bias condition C, $V_{DS} = 80$ percent of rated V_{DS} ,	I_{DSS1}		10	μA dc
Static drain to source on-state resistance	3421	$V_{GS} = 12$ V dc, condition A, pulsed (see 4.5.1), $I_D = I_{D2}$	$r_{DS(ON)1}$			
2N7587U3, 2N7587U3C					0.042	Ω
2N7589U3, 2N7589U3C					0.088	Ω
2N7591U3, 2N7591U3C					0.130	Ω
2N7593U3, 2N7593U3C					0.210	Ω
Forward voltage	4011	$V_{GS} = 0$ V dc, condition B, pulsed (see 4.5.1), $I_D = I_{D1}$	V_{SD}		1.2	V dc

See footnotes at end of table.

TABLE I. Group A inspection - Continued.

Inspection 1/	MIL-STD-750		Symbol	Limits		Unit
	Method	Condition		Min	Max	
<u>Subgroup 3</u>						
High temperature operation		T _C = T _J = +125°C				
Gate current	3411	V _{GS} = ±20 V dc, bias condition C, V _{DS} = 0 V	I _{GSS2}		±200	nA dc
Drain current	3413	V _{GS} = 0 V dc, bias condition C, V _{DS} = 80 percent of rated V _{DS}	I _{DSS2}		25	μA dc
Static drain to source on-state resistance	3421	V _{GS} = 12 V dc, condition A, pulsed (see 4.5.1), I _D = I _{D2}	r _{DS(ON)3}			
2N7587U3, 2N7587U3C					0.080	Ω
2N7589U3, 2N7589U3C					0.176	Ω
2N7591U3, 2N7591U3C					0.273	Ω
2N7593U3, 2N7593U3C					0.441	Ω
Gate to source voltage (threshold)	3403	V _{DS} ≥ V _{GS} , I _D = 1 mA dc	V _{GS(TH)2}	1.0		V dc
Low temperature operation		T _C = T _J = -55°C				
Gate to source voltage (threshold)	3403	V _{DS} ≥ V _{GS(TH)3} , I _D = 1 mA dc	V _{GS(TH)3}		5.0	V dc
<u>Subgroup 4</u>						
Forward transconductance	3475	I _D = I _{D2} , V _{DD} = 15 V dc (see 4.5.1)	g _{FS}			
2N7587U3, 2N7587U3C				14		S
2N7589U3, 2N7589U3C				13		S
2N7591U3, 2N7591U3C				10		S
2N7593U3, 2N7593U3C				8.8		S
Gate series resistance	3402	Condition A	R _G		2	Ω
<u>Subgroup 5</u>						
Safe operating area test	3474	See figure 4; tp = 10 ms min. VDS = 80 percent of max. rated VDS				
Electrical measurements		See table I, subgroup 2				
<u>Subgroup 6</u>						
Not applicable						

See footnotes at end of table.

TABLE I. Group A inspection - Continued.

Inspection <u>1/</u>	MIL-STD-750		Symbol	Limits		Unit
	Method	Condition		Min	Max	
<u>Subgroup 7</u>						
Gate charge	3471	Condition B, $I_D = I_{D1}$, $V_{GS} = 12$ V dc $V_{DD} = 50$ percent of rated V_{DS}	$Q_{G(ON)}$		50	nC
On-state gate charge and turn-off gate charge			$Q_{G(OFF)}$		50	
Gate to source charge (turn-on and turn-off)			Q_{GS1}		15	nC
			Q_{GS2}		15	
Gate to drain charge (turn-on and turn-off)	3473	Condition A, $di/dt = -100$ A/ μ s, $V_{DD} \leq 50$ V $I_D = I_{D1}$	Q_{GD1}		20	nC
			Q_{GD2}		20	
Reverse recovery time			t_{rr}		350	ns

1/ For sampling plan, see [MIL-PRF-19500](#).

2/ This test required for the following end-point measurements only:
 Group B, subgroups 2 and 3 (JANTXV).
 Group B, subgroups 3 and 4 (JANS).
 Group C, subgroup 2 and 6.
 Group E, subgroup 1.

TABLE II. Group D inspection.

Inspection 1/ 2/ 3/	MIL-STD-750		Symbol	Pre-irradiation limits		Post-irradiation limits		Unit
	Method	Conditions		R and F		R and F		
				Min	Max	Min	Max	
<u>Subgroup 1</u>								
Not applicable								
<u>Subgroup 2</u>								
T _C = + 25°C								
Steady-state total dose irradiation (V _{GS} bias) 4/	1019	V _{GS} = 12 V; V _{DS} = 0						
Steady-state total dose irradiation (V _{DS} bias) 4/	1019	V _{GS} = 0; V _{DS} = 80 percent of rated V _{DS} (pre-irradiation)						
End-point electricals:								
Breakdown voltage, drain to source 2N7587U3, 2N7587U3C 2N7589U3, 2N7589U3C 2N7591U3, 2N7591U3C 2N7593U3, 2N7593U3C	3407	Bias condition C, V _{GS} = 0; I _D = 1 mA	V _{(BR)DSS}	100 150 200 250		100 150 200 250		V dc V dc V dc V dc
Gate to source voltage (threshold)	3403	V _{DS} ≥ V _{GS} I _D = 1 mA	V _{GS(th)1}	2.0	4.0	2.0	4.0	V dc
Gate current	3411	Bias condition C, V _{GS} = +20 V; V _{DS} = 0	I _{GSSF1}		100		100	nA dc
Gate current	3411	Bias condition C, V _{GS} = -20 V; V _{DS} = 0	I _{GSSR1}		-100		-100	nA dc
Drain current	3413	Bias condition C, V _{GS} = 0 V _{DS} = 80 percent of rated V _{DS} (pre-irradiation)	I _{DSS}		10		10	μA dc
Static drain to source on-state voltage 2N7587U3, 2N7587U3C 2N7589U3, 2N7589U3C 2N7591U3, 2N7591U3C 2N7593U3, 2N7593U3C	3405	V _{GS} = 12 V; I _D = I _{D2} condition A, pulsed (see 4.5.1)	V _{DS(on)}		0.855 1.104 1.340 1.638		0.855 1.104 1.340 1.638	V dc V dc V dc V dc
Forward voltage source drain diode	4011	Bias condition C, V _{GS} = 0; I _D = I _{D1}	V _{SD}		1.2		1.2	V dc

1/ For sampling plan, see MIL-PRF-19500.

2/ Group D qualification may be performed prior to lot formation. Wafers qualified to these group D QCI requirements may be used for any other specification sheets utilizing the same die design.

3/ At the manufacturer's option, group D samples need not be subjected to the screening tests, and may be assembled in its qualified package or in any qualified package that the manufacturer has data to correlate the performance to the designated package.

4/ Separate samples shall be pulled for each bias.

* TABLE III. Group E inspection (all quality levels) for qualification or re-qualification only.

Inspection	MIL-STD-750		Sample plan
	Method	Conditions	
<u>Subgroup 1</u>			45 devices c = 0
Temperature cycling	1051	-55°C to +150°C, 500 cycles	
Hermetic seal	1071	As applicable.	
Fine leak			
Gross leak			
Electrical measurements		See table I , subgroup 2 herein.	
<u>Subgroup 2 1/</u>			45 devices c = 0
Steady-state gate bias	1042	Condition B, 1,000 hours.	
Electrical measurements		See table I , subgroup 2 herein.	
Steady-state reverse bias	1042	Condition A, 1,000 hours.	
Electrical measurements		See table I , subgroup 2 herein.	
<u>Subgroup 3</u>			n = 45, c = 0
Switching time test	3472	$I_D = I_{D1}$, $V_{GS} = 12$ Vdc, $R_G = 7.5 \Omega$, $V_{DD} = 50$ percent rated V_{DS} Maximum measurements: $t_{d(on)} = 25$ ns; $t_r = 30$ ns; $t_{d(off)} = 60$ ns; $t_f = 30$ ns	
<u>Subgroup 4</u>			Sample size N/A
Thermal impedance curves		See MIL-PRF-19500 .	
<u>Subgroup 5</u>			3 devices c = 0
Barometric pressure	1001	To 70,000 feet ()	
2N7593U3, 2N7593U3C only			
<u>Subgroup 10</u>			22 devices c = 0
Commutating diode for safe operating area test procedure for measuring dv/dt during reverse recovery of power MOSFET transistors or insulated gate bipolar transistors.	3476		

1/ A separate sample for each test shall be pulled.

2/ Group E qualification of SEE effect testing may be performed prior to lot formation. Qualification may be extended to other specification sheets utilizing the same structurally identical die design.

3/ Device qualification to a higher level LET is sufficient to qualify all lower level LETs.

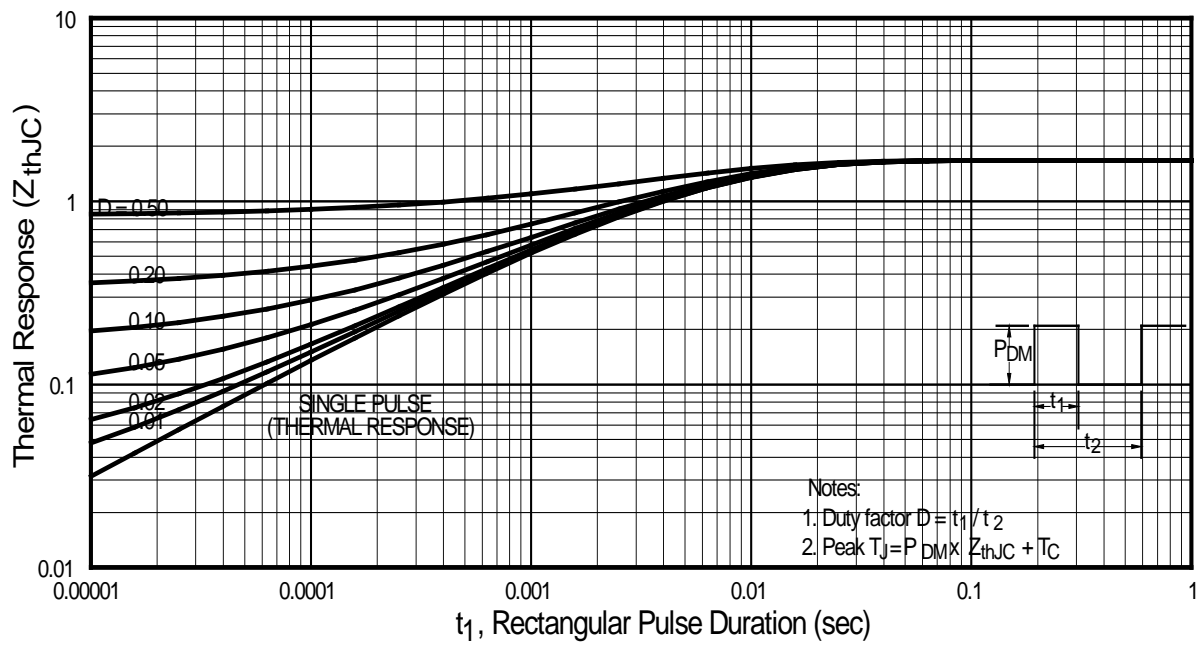
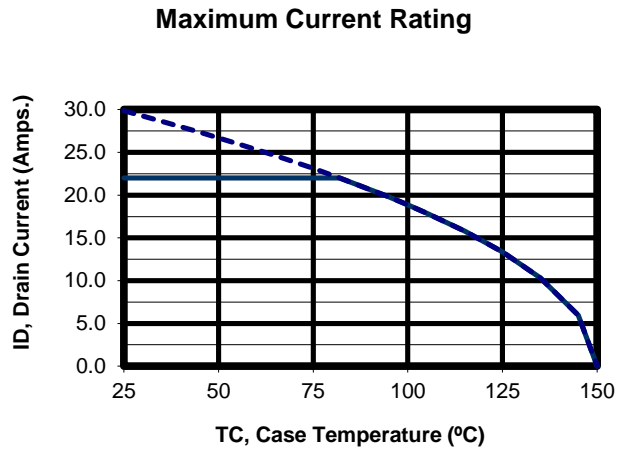
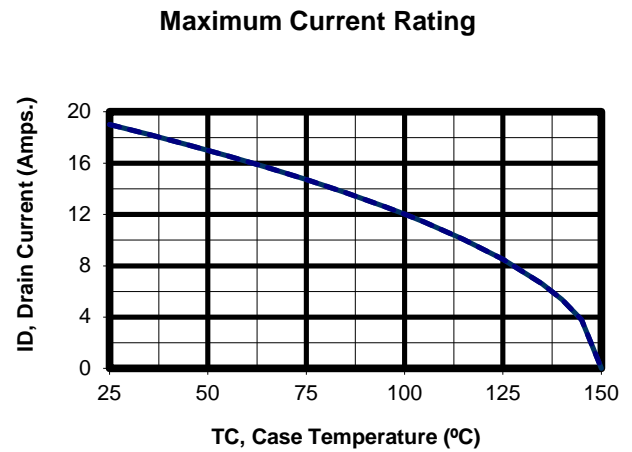


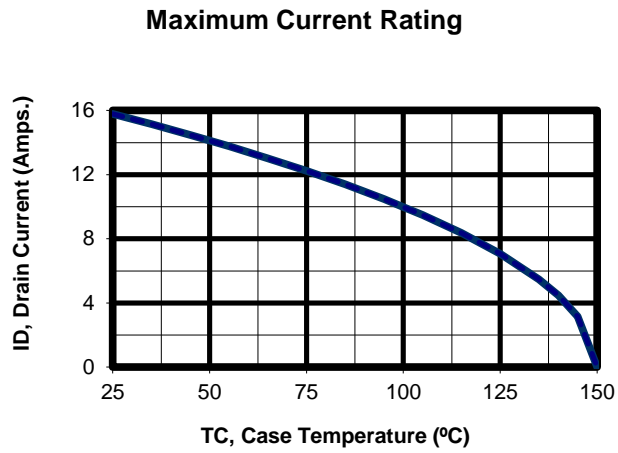
FIGURE 2. Thermal response curve.



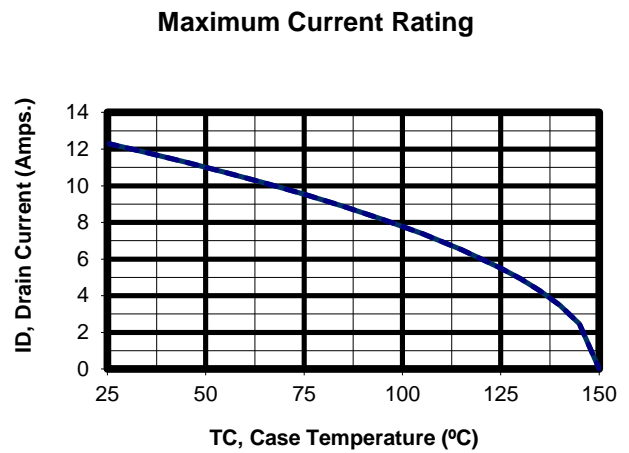
2N7587U3, 2N7587U3C



2N7589U3, 2N7589U3C



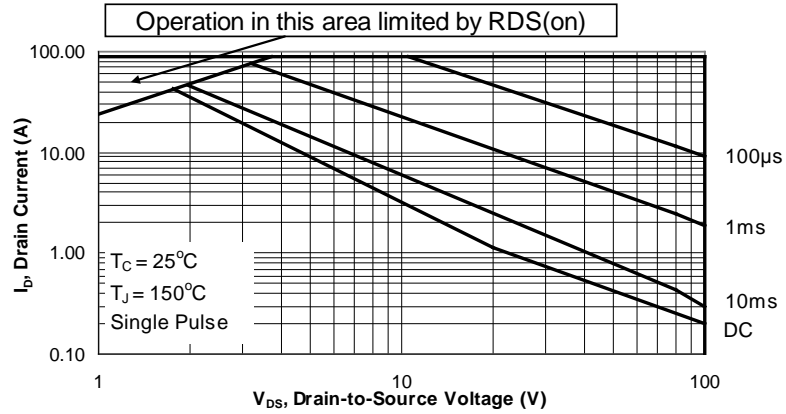
2N7591U3, 2N7591U3C



2N7593U3, 2N7593U3C

FIGURE 3. Maximum drain current versus case temperature graphs.

2N7587U3, 2N7587U3C



2N7589U3, 2N7589U3C

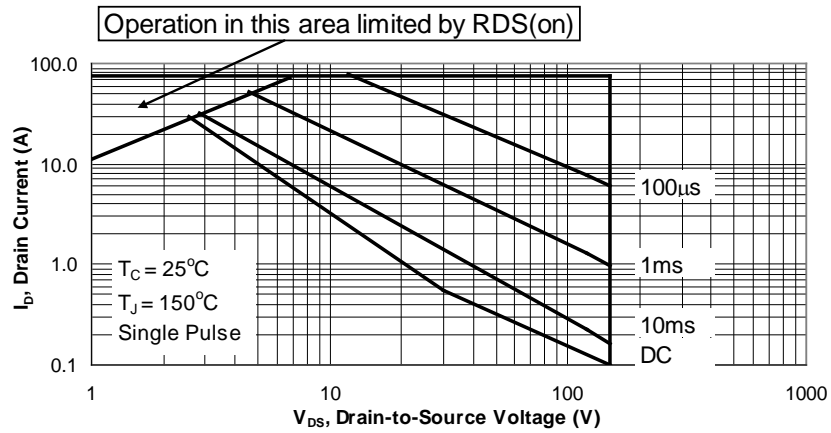
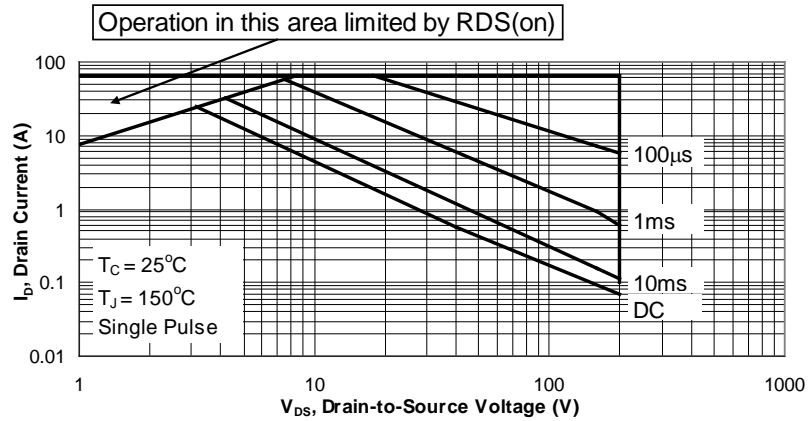


FIGURE 4. Safe operating area graph.

2N7591U3, 2N7591U3C



2N7593U3, 2N7593U3C

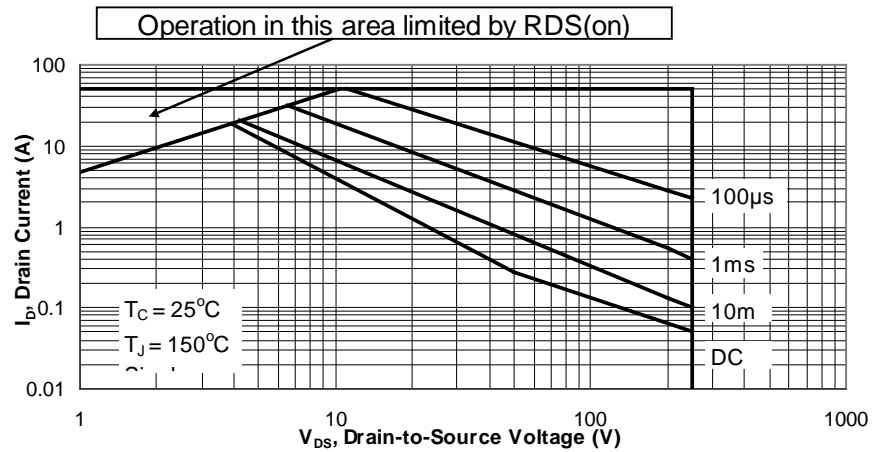


FIGURE 4. Safe operating area graph - Continued.

5. PACKAGING

5.1 Packaging. For acquisition purposes, the packaging requirements shall be as specified in the contract or order (see 6.2). When packaging of material is to be performed by DoD or in-house contractor personnel, these personnel need to contact the responsible packaging activity to ascertain packaging requirements. Packaging requirements are maintained by the Inventory Control Point's packaging activities within the Military Service or Defense Agency, or within the Military Service's system commands. Packaging data retrieval is available from the managing Military Department's or Defense Agency's automated packaging files, CD-ROM products, or by contacting the responsible packaging activity.

6. NOTES

(This section contains information of a general or explanatory nature that may be helpful, but is not mandatory. The notes specified in [MIL-PRF-19500](#) are applicable to this specification.)

6.1 Intended use. Semiconductors conforming to this specification are intended for original equipment design applications and logistic support of existing equipment.

* 6.2 Acquisition requirements. Acquisition documents should specify the following:

- a. Title, number, and date of this specification.
- b. Packaging requirements (see 5.1).
- c. Lead finish (see 3.4.1).
- d. The complete PIN, see 1.5.

* 6.3 Qualification. With respect to products requiring qualification, awards will be made only for products which are, at the time of award of contract, qualified for inclusion in Qualified Manufacturers List (QML 19500) whether or not such products have actually been so listed by that date. The attention of the contractors is called to these requirements, and manufacturers are urged to arrange to have the products that they propose to offer to the Federal Government tested for qualification in order that they may be eligible to be awarded contracts or orders for the products covered by this specification. Information pertaining to qualification of products may be obtained from DLA Land and Maritime, ATTN: VQE, P.O. Box 3990, Columbus, OH 43218-3990 or e-mail vqe.chief@dla.mil. An online listing of products qualified to this specification may be found in the Qualified Products Database (QPD) at <https://assist.dla.mil>.

6.4 Substitution information. Devices covered by this specification are substitutable for the manufacturer's and user's Part or Identifying Number (PIN) (without JAN and RHA prefix). This information in no way implies that manufacturer's PINs are substitutable for the military PIN.

Preferred types military PIN	Commercial PIN
2N7587U3 2N7589U3 2N7591U3 2N7593U3	IRHNJ67130 IRHNJ67134 IRHNJ67230 IRHNJ67234
2N7587U3C 2N7589U3C 2N7591U3C 2N7593U3C	IRHNJC67130 IRHNJC67134 IRHNJC67230 IRHNJC67234

6.5 Application data.

6.5.1 Manufacturer specific irradiation data. Each manufacturer qualified to this slash sheet has characterized its devices to the requirements of [MIL-STD-750](#) method 1080 and as specified herein. Since each manufacturer's characterization conditions can be different and can vary by the version of method 1080 qualified to, the MIL-STD-750 method 1080 revision version date and conditions used by each manufacturer for characterization have been listed here (see table IV) for information only. SEE conditions and figures listed in section 6 are current as of the date of this specification sheet, please contact the manufacturer for the most recent conditions.

* TABLE IV. Manufacturers characterization conditions.

Manufacturers CAGE	Inspection	MIL-STD-750		Sample plan
		Method	Conditions	
69210 (Applicable to devices with a date code of September 2009 and older)	SEE <u>1/</u>	1080	See MIL-STD-750 method 1080	3 devices
	Electrical measurements		I_{GSSF1} , I_{GSSR1} , and I_{DSS1} in accordance with table I , subgroup 2	
	SEE irradiation		Fluence = $3E5 \pm 20$ percent ions/cm ² Flux = $2E3$ to $2E4$ ions/cm ² /sec, temperature = $25 \pm 5^\circ\text{C}$	
	2N7587U3, 2N7587U3C		Surface LET = 39 MeV-cm ² /mg $\pm 5\%$, range = $40 \mu\text{m} \pm 7.5\%$, energy = 315 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 100 \text{ V}$ and $V_{GS} = -19 \text{ V}$; $V_{DS} = 40 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (Typical 3.80 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7589U3, 2N7589U3C		Surface LET = 39 MeV-cm ² /mg $\pm 5\%$, range = $50 \mu\text{m} \pm 5\%$, energy = 410 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 150 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (Typical 4.90 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7591U3, 2N7591U3C		Surface LET = 42 MeV-cm ² /mg $\pm 5\%$, range = $205 \mu\text{m} \pm 5\%$, energy = 2450 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 200 \text{ V}$ and $V_{GS} = -10 \text{ V}$; $V_{DS} = 190 \text{ V}$ and $V_{GS} = -15 \text{ V}$ (Typical 8.49 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7593U3, 2N7593U3C		Surface LET = 44 MeV-cm ² /mg $\pm 5\%$, range = $125 \mu\text{m} \pm 10\%$, energy = 1350 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 250 \text{ V}$ and $V_{GS} = -15 \text{ V}$, $V_{DS} = 40 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (Typical 10.05 MeV/Nucleon at Texas A & M Cyclotron)	
	Electrical measurements		I_{GSSF1} , I_{GSSR1} , and I_{DSS1} in accordance with table I , subgroup 2	

* TABLE IV. Manufacturers characterization conditions – continued.

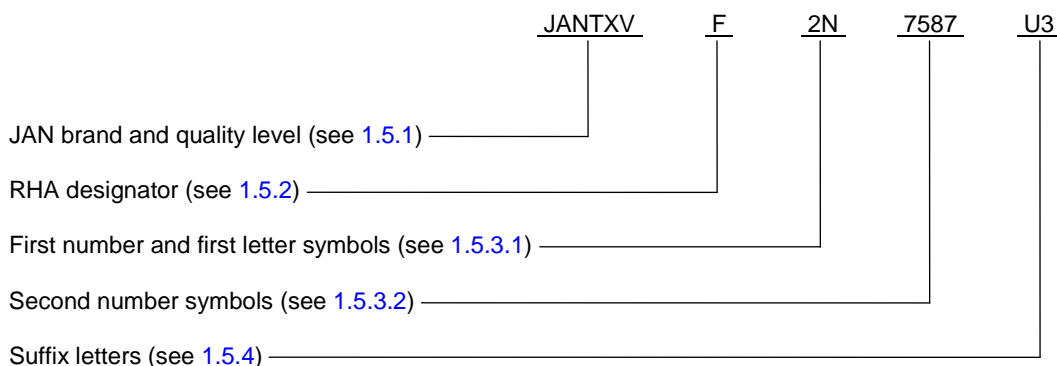
Manufacturers CAGE	Inspection	MIL-STD-750		Sample plan
		Method	Conditions	
69210 (Applicable to devices with a date code of September 2009 and older)	SEE 1/	1080	See MIL-STD-750 method 1080	3 devices
	Electrical measurements		I_{GSSF1} , I_{GSSR1} , and I_{DSS1} in accordance with table I , subgroup 2	
	SEE irradiation		Fluence = $3E5 \pm 20$ percent ions/cm ² Flux = $2E3$ to $2E4$ ions/cm ² /sec, temperature = $25 \pm 5^\circ\text{C}$	
	2N7587U3, 2N7587U3C		Surface LET = 61 MeV-cm ² /mg $\pm 5\%$, range = $32 \mu\text{m} \pm 7.5\%$, energy = 345 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 100 \text{ V}$ and $V_{GS} = -10 \text{ V}$; $V_{DS} = 30 \text{ V}$ and $V_{GS} = -15 \text{ V}$ (Typical 2.70 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7589U3, 2N7589U3C		Surface LET = 61 MeV-cm ² /mg $\pm 5\%$, range = $66 \mu\text{m} \pm 7.5\%$, energy = 825 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 150 \text{ V}$ and $V_{GS} = -10 \text{ V}$; $V_{DS} = 40 \text{ V}$ and $V_{GS} = -15 \text{ V}$ (Typical 6.40 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7591U3, 2N7591U3C		Surface LET = 61 MeV-cm ² /mg $\pm 5\%$, range = $66 \mu\text{m} \pm 7.5\%$, Energy = 825 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 200 \text{ V}$ and $V_{GS} = -15 \text{ V}$; $V_{DS} = 190 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (Typical 6.41 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7593U3, 2N7593U3C		Surface LET = 61 MeV-cm ² /mg $\pm 5\%$, range = $66 \mu\text{m} \pm 7.5\%$, Energy = 825 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 250 \text{ V}$ and $V_{GS} = -10 \text{ V}$; $V_{DS} = 50 \text{ V}$ and $V_{GS} = -15 \text{ V}$ (Typical 6.41 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7587U3, 2N7587U3C		Surface LET = 90 MeV-cm ² /mg $\pm 5\%$, range = $29 \mu\text{m} \pm 7.5\%$, Energy = 375 MeV $\pm 7.5\%$ In-situ bias conditions: $V_{DS} = 100 \text{ V}$ and $V_{GS} = -5 \text{ V}$ (Typical 1.88 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7589U3, 2N7589U3C		Surface LET = 90 MeV-cm ² /mg $\pm 5\%$, range = $80 \mu\text{m} \pm 5\%$, Energy = 1470 MeV $\pm 5\%$ In-situ bias conditions: $V_{DS} = 50 \text{ V}$ and $V_{GS} = -5 \text{ V}$; $V_{DS} = 30 \text{ V}$ and $V_{GS} = -10 \text{ V}$ (Typical 7.47 MeV/Nucleon at Texas A & M Cyclotron)	
	Electrical measurements		I_{GSSF1} , I_{GSSR1} , and I_{DSS1} in accordance with table I , subgroup 2	

* TABLE IV. Manufacturers characterization conditions – continued.

Manufacturers CAGE	Inspection	MIL-STD-750		Sample plan
		Method	Conditions	
69210 (Applicable to devices with a date code of September 2009 and older)	SEE <u>1/</u>	1080	See MIL-STD-750 method 1080	3 devices
	Electrical measurements		I_{GSSF1} , I_{GSSR1} , and I_{DSS1} in accordance with table I , subgroup 2	
	2N7591U3, 2N7591U3C		Surface LET = 90 MeV-cm ² /mg \pm 5%, Range = 80 μ m \pm 5%, Energy = 1470 MeV \pm 5% In-situ bias conditions: V_{DS} = 170 V and V_{GS} = -5 V (Typical 7.47 MeV/Nucleon at Texas A & M Cyclotron)	
	2N7593U3, 2N7593U3C		Surface LET = 90 MeV-cm ² /mg \pm 5%, Range = 80 μ m \pm 5%, Energy = 1470 MeV \pm 5% In-situ bias conditions: V_{DS} = 75 V and V_{GS} = -5 V (Typical 7.47 MeV/Nucleon at Texas A & M Cyclotron)	
	Electrical measurements		I_{GSSF1} , I_{GSSR1} , and I_{DSS1} in accordance with table I , subgroup 2	
Upon qualification, all manufacturers will provide the verification test conditions to be added to this table.				

1/ I_{GSSF1} , I_{GSSR1} , and I_{DSS1} was examined before and following SEE irradiation to determine acceptability for each bias conditions. Other test conditions in accordance with [table I](#), subgroup 2, may be performed at the manufacturer's option.

- * 6.6 PIN construction example. The PINs for encapsulated devices are constructed using the following form.



- * 6.7 List of PINs. The following is a list of possible PINs (without JAN brand) available on this specification sheet.

TXV2NF7587U3	TXV2NF7589U3	TXV2NF7591U3	TXV2NF7593U3
TXV2NR7587U3	TXV2NR7589U3	TXV2NR7591U3	TXV2NR7593U3
TXV2NF7587U3C	TXV2NF7589U3C	TXV2NF7591U3C	TXV2NF7593U3C
TXV2NR7587U3C	TXV2NR7589U3C	TXV2NR7591U3C	TXV2NR7593U3C
S2NF7587U3	S2NF7589U3	S2NF7589U3	S2NF7593U3
S2NR7587U3	S2NR7589U3	S2NR7589U3	S2NR7593U3
S2NF7587U3C	S2NF7589U3C	S2NF7589U3C	S2NF7593U3C
S2NR7587U3C	S2NFR589U3C	S2NR7589U3C	S2NR7593U3C

- * 6.8 Changes from previous issue. The margins of this specification are marked with asterisks to indicate where changes from the previous issue were made. This was done as a convenience only and the Government assumes no liability whatsoever for any inaccuracies in these notations. Bidders and contractors are cautioned to evaluate the requirements of this document based on the entire content irrespective of the marginal notations and relationship to the previous issue.

Custodians:
 Army - CR
 Navy - EC
 Air Force - 85
 NASA - NA
 DLA - CC

Preparing activity:
 DLA - CC

(Project 5961-2014-124)

Review activity:
 Army - MI

NOTE: The activities listed above were interested in this document as of the date of this document. Since organizations and responsibilities can change, you should verify the currency of the information above using the ASSIST Online database at <https://assist.dla.mil>.